

PELLICLE MEMBRANE

ABSTRACT

The purpose of the present invention is to produce a
5 pellicle film, which is suppressed in light deterioration or
photodecomposition due to lithography light exposure, by
simpler processes. Specifically disclosed is a pellicle film
for lithography containing an amorphous fluoropolymer,
which is characterized by containing 5-800 ppm by mass of a
10 fluorine-based solvent. Also specifically disclosed is a
method for producing a pellicle film, which comprises: a
step A wherein a coating film of a solution that contains an
amorphous fluoropolymer and a fluorine-based solvent is
formed; and a step B wherein the fluorine-based solvent in
15 the coating film is removed. The method for producing a
pellicle film is characterized in that 5-800 ppm by mass of
the fluorine-based solvent is caused to remain in the coating
film in the step B.